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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/759,641	01/16/2004		Han-Ming Wu	42P10058D	1204
8791	7590	04/04/2006		EXAMINER	
BLAKELY	SOKOL	OFF TAYLOR &	NGUYEN, HUNG		
		DULEVARD	ART UNIT	PAPER NUMBER	
SEVENTH I		90025-1030	2851		
	,			DATE MAILED: 04/04/200	6

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office Action Commons	10/759,641	WU ET AL.				
Office Action Summary	Examiner	Art Unit				
	Hung Henry V. Nguyen	2851				
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication. - Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).						
Status						
1) Responsive to communication(s) filed on 06 M	arch 2006.					
2a) This action is FINAL . 2b) ⊠ This	action is non-final.					
3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is						
closed in accordance with the practice under E	x parte Quayle, 1935 C.D. 11, 45	3 O.G. 213.				
Disposition of Claims						
 4) Claim(s) 51,52,54,55 and 64-80 is/are pending in the application. 4a) Of the above claim(s) is/are withdrawn from consideration. 5) Claim(s) 68 is/are allowed. 6) Claim(s) 51,52,54,55,64-67 and 69-80 is/are rejected. 7) Claim(s) is/are objected to. 8) Claim(s) are subject to restriction and/or election requirement. 						
Application Papers						
 9) ☐ The specification is objected to by the Examiner. 10) ☑ The drawing(s) filed on 1/16/04 is/are: a) ☑ accepted or b) ☐ objected to by the Examiner. Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a). Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152. 						
Priority under 35 U.S.C. § 119						
 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some * c) None of: 1. Certified copies of the priority documents have been received. 2. Certified copies of the priority documents have been received in Application No 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)). * See the attached detailed Office action for a list of the certified copies not received. 						
Attachment(s) 1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	4) Interview Summary Paper No(s)/Mail Da 5) Notice of Informal Pa					

DETAILED ACTION

Continued Examination Under 37 CFR 1.114

1. A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on 3/6/2006 has been entered.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

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3. Claims 78 and 80 are rejected under 35 U.S.C. 102(e) as being anticipated by Shirasaki (U.S.Pat. 6,593,034).

With respect to claim 78, Shirasaki discloses an apparatus and corresponding method comprising substantially all limitations of the instant claims such as: adding a first gas/inert gas to an enclosure (10) filled with a second gas/air through one slit (6) wherein the first gas is inert gas (for example: nitrogen) which has less total oxygen and carbon than the second gas which is air and the first gas/inert gas having a different gas composition than the second gas/air (see col.4, lines 58-64), and the enclosure (10) being between a mask protective device (1), a patterned mask (5) and a wall (2) connecting the mask protective device with the pattern mask and removing the second gas from the enclosure through one outlet port (see col. 3, lines 58-67). Applicant argues that Shirasaki does not suggest "adding a first gas to an enclosure having a second gas through one or more slits aligned with a length of a side of the enclosure to distribute a flow of the first gas over the length of the side of the enclosure"; the Examiner respectfully disagrees with the applicant. Due to the alternative recitation of "one or more slits", Shirasaki therefore meets the recitation as claimed since Shirasaki discloses adding a first gas/inert gas to an enclosure (10) filled with a second gas/air through one slit (6) aligned with a length of a side of the enclosure (10) to distribute a flow of the inert gas/first gas over the length of the side of the enclosure (see figure 2).

As to claim 80, Shirasaki teaches removing the second gas including removing the second gas through one slit (6) or "to a gas-discharge line (not shown in the figure)" (see col.4, lines 50-51).

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Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 5. Claims 51-52, 64-66, 69-72, 74-76 and 79 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shirasaki (U.S.Pat. 6,593,034) in view of Shirakawa et al (U.S.Pat. 6,380,518).

With respect to claims 51-52, 64-66, 69-72, 74-76, and 79, Shirasaki discloses an apparatus and corresponding method comprising substantially all limitations of the instant claims such as: adding a first gas/inert gas to an enclosure (10) filled with a second gas/air through a vent (6) wherein the first gas is inert gas (for example: nitrogen) which has less total oxygen and carbon than the second gas which is air and the first gas/inert gas having a different gas composition than the second gas/air (see col.4, lines 58-64), and the enclosure (10) being between a mask protective device (1), a patterned mask (5) and a wall (2) connecting the mask protective device with the pattern mask and removing the second gas from the enclosure through the vent (see col.3, lines 60-67). Shirasaki does not expressly disclose the inlet port having "a plurality of discrete openings arranged" or "at least five openings" or "a vent including a plurality of openings" to distribute a flow of the first gas over a length of a side of the enclosure, as recited in the claims of the present application. However, Shirasaki suggests adding the first gas through "at least one but not all of the gas-passage openings in the pellicle frame and

discharging the gas through the rest of the gas-passage openings" (see col.3, lines 62-67).

Furthermore, it has been held that mere duplication of the essential working parts of a device involves only routine skill in the art, St. Regis Paper Co.v. Bemis Co., 193 USPQ 8. For example, Shirakawa et al (figure 7) teaches supplying gas into a chamber via a gas supply system (91) having a plurality of discrete ports (63) and removing the gas via an exhaust mechanism (92) having a plurality of exhaust discrete ports (66a, 66b). In view of such suggestion and teachings, it would have been obvious to a skilled artisan to utilize an inlet port having a plurality of discrete openings" or "at least five openings" as taught by Shirakawa on a same side of the enclosure of Shirasaki for adding the first gas into the enclosure. The at least purpose of doing so would have been to quickly supply the gas to the enclosure and to equalize pressure of the supplied gas across the pellicle whereby the distortion of the pellicle can be prevented.

6. Claims 54-55 and 73, 77 are rejected under 35 U.S.C. 103(a) as being unpatentable over Shirasaki (U.S.Pat. 6,593,034) in view of Shirakawa et al (U.S.Pat. 6,380,518) and further in view of Ivaldi (U.S.Pat. 6,507,390).

As to claims 54 and 77, Shirasaki as modifiged by Shirakawa, discloses a method comprising substantially all of the limitations of the instant claims as discussed above. Shirasaki as modified by Shirakawa lacks to show removing the second gas by vacuum. Ivaldi teaches a vacuum source (418) for removing the second gas/air. It would have been obvious to one having ordinary skill in the art at the time the invention was made to combine the teachings of Shirasaki, Shirakawa and Ivaldi to obtain the invention as specified in claims 54 and 77 of the present invention. It would have been obvious to a skilled artisan to utilize a vacuum source as taught

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by Ivaldi into the method of Shirasaki as modified by Shirakawa et al for the purpose of removing the second gas from the enclosure.

As to claims 55, and 73, Shirasaki as modified by Shirakawa and Ivaldi, lacks to show the inlet opening being smaller than the outlet opening. However, such a modification would have involved a mere change in the size of a component. A change in size is generally recognized as being within the level of ordinary skill in the art. *In re Rose*, 105 USPQ 237 (CCPA 1955). Furthermore, Ivaldi suggests that "the purge gas is inserted at a rate slowly enough so as not to cause substantially distortion to reticle 104 and or pellicle 206" (see col.8, lines 15-17). In view of such teachings, it would have been obvious to a skill artisan to make the inlet opening smaller than the outlet opening so that the rate of the second gas/purge gas supplied to the enclosure is slower than the rate of the second gas removed from the enclosure. The purpose of doing so would have been to prevent the pressure of the enclosure from being so high that could damage the reticle and or pellicle as suggested by Ivaldi.

7. Claim 67 is rejected under 35 U.S.C. 103(a) as being unpatentable over Shirasaki (U.S.Pat. 6,593,034) in view of Shirakawa et al (U.S.Pat. 6,380,518) and further in view of Shimada (U.S.Pat. 5,735,961).

With respect to claim 67, Shirasaki as modified by Shirakawa, discloses a method comprising substantially all of the limitations of the instant claims as discussed above but does not expressly disclose adding the first gas to the enclosure by diffusion and/or removing the second gas from the enclosure by diffusion. However, suitable gas supply system and purge gas system using pressure, diffusion or vacuum, are well known in the art. For example, Shimada

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teaches a semiconductor fabricating apparatus where the inert gas is supplied to a chamber by diffusion fashion (see col.2, lines 13-16). It would have been obvious to one having ordinary skill in the art at the time the invention was made to combine the teachings of Shimada, Shirasaki and Shirakawa to obtain the invention as specified in the above claim of the instant application. It would have been obvious to a skilled artisan to add and remove the first gas and second gas from the enclosure of Shirasaki as modified by Shirakawa by using diffusion fashion as suggested by Shimada for at least the purpose of effectively eliminating distortion of either the mask or mask protective device due to pressure changes.

Allowable Subject Matter

8. Claim 68 is allowed with the reasons set forth in the previous office action.

Response to Amendment/Arguments

- 9. Applicant's amendment filed March 6, 2006 has been entered. Claims 51, 64, 66, 68, 69, 71 have been amended. Claims 53, 56-63 have been cancelled. New claims 78-80 have been added. Applicant's arguments with respect to prior art have been carefully reviewed. They have been fully addressed and traversed in view of new grounds of rejections as set forth above.
- 10. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Hung Henry V. Nguyen whose telephone number is 571-272-2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on 571-272-2258. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Hung Henry V Nguyen Primary Examiner

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hvn 3/30/06